



SHEET 1 of 3

FORM PTO - 1449

SUPPLEMENTAL INFORMATION DISCLOSURE  
STATEMENT

ATTY DOCKET NO.: ASX-015C4

APPLICANTS: Smith et al.

SERIAL NO.: 10/689,165

FILING DATE: October 20, 2003

GROUP: 2821

## U.S. PATENT DOCUMENTS

EXAM INIT.		DOCUMENT NO.	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>mm</i>	A127	2,981,902	04/25/1961	Familier	333	17	06/22/1959
	A128	3,509,500	04/28/1970	McNair et al.	334	47	12/05/1966
	A129	3,794,941	02/26/1974	Templin	333	17	05/08/1972
	A130	3,906,405	09/16/1975	Kommrusch	333	17	07/01/1974
	A131	4,095,198	06/13/1978	Kirby	333	32	01/31/1977
	A132	4,201,960	05/06/1980	Skutta et al.	333	17	05/24/1978
	A133	4,486,722	12/04/1984	Landt	333	17	02/18/1982
	A134	4,486,723	12/04/1984	Lysobey	333	17	01/06/1983
	A135	5,277,751	01/11/1994	Ogle	156	643	06/18/1992
	A136	5,458,732	10/17/1995	Butler et al.	216	61	01/28/1994
	A137	5,474,648	12/12/1995	Patrick et al.	156	627.1	07/29/1994
	A138	5,573,595	11/12/1996	Dible	118	723 MP	09/29/1995
	A139	5,618,382	04/08/1997	Mintz et al.	216	64	06/25/1993
	A140	5,643,364	07/01/1997	Zhao et al.	118	723	05/02/1996
	A141	5,670,881	09/23/1997	Arakawa et al.	324	322	02/09/1996
<i>mm</i>	A142	6,424,232	07/23/2002	Mavretic et al.	333	17.3	11/30/1999

EXAMINER

Mark Pascnall  
Primary Examiner

DATE CONSIDERED

3/5/05

FORM PTO - 1449				ATTY DOCKET NO.: ASX-015C4					
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT				APPLICANTS: Smith et al. SERIAL NO.: 10/689,165 FILING DATE: October 20, 2003 GROUP: 2821					
<b>U.S. PATENT DOCUMENTS</b>									
EXAM INIT.		DOCUMENT NO.	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE		
M	A143	6,459,066	10/01/2002	Khater et al.	219	121.41	06/08/2001		
<b>FOREIGN PATENT DOCUMENTS</b>									
EXAM INIT.		DOCUMENT NO.	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG (Y/N)
M	B7	39 42 560 C2	05/02/1996	DE				NO	YES - Translation
m	B8	2056702	03/20/1996	RU				NO	NO
n	B9	2094961	10/27/1997	RU				NO	NO
<b>OTHER ART, JOURNAL ARTICLES, ETC.</b>									
EXAM INIT.		OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)							
M	C126	Heckman et al., Advanced Energy Marketing Materials, "The Evolution of RF Power Delivery in Plasma Processing," (Copyright 1998) pp. 1-8.							
M	C127	Advanced Energy Marketing Materials, "Introducing Power Supplies and Plasma Systems," (Copyright 1992) pp. 1-8.							
M	C128	Advanced Energy Marketing Materials, "Impedance Matching," (Copyright 1992) pp. 1-8.							
n	C129	Advanced Energy Industries, Inc., Presentation "Advances in 13.56 MHz Applications" by Knipp (date unknown) pp. 1-32.							
M	C130	<u>CRC Handbook of Chemistry and Physics</u> (1979-1980) pp. E-60.							
M	C131	Eckert, "The Hundred Year History of Induction Discharges," <u>Proceedings of The Second Annual International Conference of Plasma Chemistry and Technology</u> (November 12-13, 1984) pp 171-202.							
EXAMINER					Mark Paschall Primary Examiner				
					DATE CONSIDERED 3/5/05				

FORM PTO - 1449		ATTY DOCKET NO.: ASX-015C4
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT		APPLICANTS: Smith et al.
		SERIAL NO.: 10/689,165
		FILING DATE: October 20, 2003
		GROUP: 2821
OTHER ART, JOURNAL ARTICLES, ETC.		
EXAM INIT.		OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)
M	C132	Foutz, "Switching-Mode Power Supply Design" (January 17, 2001) pp. 1-3.
↑	C133	Gale et al., "Characterization of a Micromachined Electrical Field-Flow Fractionation ( $\mu$ EFF) System" (no date) pp. 1-6.
	C134	"An Intelligent Solution to RF Load-Power Variability," Vol. 2, No. 3, 3 <sup>rd</sup> Quarter (1995) pp 1-8.
	C135	Lenk, "Switching Power-Supply Basics," <u>Simplified Design of Switching Power Supplies</u> (1995) pp. 1.
	C136	"Linear Circuit Analysis," <u>Electrical Engineering Handbook</u> , (Copyright 1993) pp. 85.
	C137	Massey, "Fabric antennas for mobile telephony integrated within clothing" (no date) pp. 1-4.
	C138	Memorandum Opinion, US District Court for the District of Delaware dated February 12, 2004.
	C139	Order, US District Court for the District of Delaware dated February 12, 2004.
	C140	Pressman, <u>Switching Power Supply Design</u> , (no date) pp. xvii.
	C141	"Principals and Techniques," <u>Electrical Engineers' Handbook</u> , (Copyright 1997) pp. 3.40-3.41.
	C142	<u>Remote Plasma Source</u> Chapter 2, (March 2001) pp. 2-1 - 2-6.
	C143	Ulanov et al., "Study of the Transformer-Coupled Induction Toroidal Discharge for Development of Plasma-Chemical Reactors and New Light Sources," (date unknown) pp. 1-19.
↓ M	C144	Talanov et al., "Measurement of the absolute penetration depth and surface resistance of superconductors and normal metals with the variable spacing parallel plate resonator," <u>Review of Scientific Instruments</u> , Vol. 71, No. 5 (May 2000) pp. 2136-2146.
EXAMINER		DATE CONSIDERED
Mark Paschall		3/5/05
Primary Examiner		

<b>FORM PTO - 1449</b>				<b>ATTY DOCKET NO.:</b> ASX-015C4			
<b>INFORMATION DISCLOSURE STATEMENT</b>				<b>APPLICANTS:</b> Smith et al.			
				<b>SERIAL NO.:</b> Not yet assigned.			
				<b>FILING DATE:</b> Herewith			
				<b>GROUP:</b> Not yet assigned.			
<b>U.S. PATENT DOCUMENTS</b>							
EXAM INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>m</i>	AA	5,290,382	03/01/94	Zarowin et al.			
	AB	3,343,022	09/19/67	Eckert			
	AC	4,431,901	02/14/84	Hull			
	AD	4,878,149	10/31/89	Stichl et al.			
	AE	5,346,578	09/13/94	Benzing et al.			
	AF	5,401,350	03/28/95	Patrick et al.			
	AG	5,405,480	04/11/95	Benzing et al.			
	AH	5,430,355	07/04/95	Paranjpe			
	AI	5,468,296	11/21/95	Patrick et al.			
	AJ	5,479,072	12/26/95	Dakin et al.			
	AK	5,506,507	04/09/96	Schwierzke et al.			
	AL	5,514,246	05/07/96	Blalock			
	AM	3,500,118	03/10/70	Anderson			
	AN	3,663,361	05/16/72	Yoshikawa			
	AO	3,987,334	10/19/76	Anderson			
	AP	4,088,926	05/09/78	Fletcher et al.			
	AQ	4,180,763	12/25/79	Anderson			
	AR	4,252,609	02/24/81	Kerst et al.			
	AS	4,626,400	12/02/86	Jassby et al.			
	AT	4,689,192	08/25/87	Nagata			
	AU	5,254,830	10/19/93	Zarowin et al.			
	AV	5,336,355	08/09/94	Zarowin et al.			
	AW	5,556,549	09/17/96	Patrick et al.			
	AX	5,630,880	05/20/97	Eastlund			
	AY	H554	12/06/88	Dawson et al.			
<i>m</i>	AZ	4,431,898	02/14/84	Reinberg et al.			
<b>EXAMINER</b> Mark Paschnall Primary Examiner				<b>DATE CONSIDERED</b> 3/5/05			

<b>FORM PTO - 1449</b>				<b>ATTY DOCKET NO.:</b> ASX-015C4			
<b>INFORMATION DISCLOSURE STATEMENT</b>				<b>APPLICANTS:</b> Smith et al.			
				<b>SERIAL NO.:</b> Not yet assigned.			
				<b>FILING DATE:</b> Herewith			
				<b>GROUP:</b> Not yet assigned.			
<b>U.S. PATENT DOCUMENTS</b>							
EXAM INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>m</i>	A1	H627	04/04/89	Peng			
	A2	Des. 384,173	09/23/97	Godyak et al.			
	A3	4,049,940	09/20/97	Moisan et al.			
	A4	4,065,369	12/27/77	Ogawa et al.			
	A5	4,285,800	08/25/81	Welty			
	A6	4,324,611	04/13/82	Vogel et al.			
	A7	4,350,578	09/21/82	Frieser et al.			
	A8	4,368,092	01/11/83	Steinberg et al.			
	A9	4,461,954	07/24/84	Inoue			
	A10	4,631,105	12/23/86	Carroll et al.			
	A11	4,668,336	05/26/87	Shimkunas			
	A12	4,668,366	05/26/87	Zarowin			
	A13	4,793,975	12/27/88	Drage			
	A14	4,810,933	03/07/89	Moisan et al.			
	A15	4,853,250	08/01/89	Boulos et al.			
	A16	4,859,908	08/22/89	Yoshida et al.			
	A17	4,897,282	01/30/90	Kniseley et al.			
	A18	4,906,898	03/06/90	Moisan			
	A19	4,948,458	08/14/90	Ogle			
	A20	5,000,771	03/19/91	Fleming, Jr. et al.			
	A21	5,008,593	04/16/91	Schlie et al.			
	A22	5,016,332	05/21/91	Reichelderfer, deceased et al.			
	A23	5,099,100	03/24/92	Bersin et al.			
	A24	5,144,196	09/01/92	Gegenwart et al.			
	A25	5,180,150	01/19/93	Prusak et al.			
<i>m</i>	A26	5,198,718	03/30/93	Davis et al.			
<b>EXAMINER</b> Mark Paschall Primary Examiner				<b>DATE CONSIDERED</b> 3/5/05			

<b>FORM PTO - 1449</b>				<b>ATTY DOCKET NO.:</b> ASX-015C4			
<b>INFORMATION DISCLOSURE STATEMENT</b>				<b>APPLICANTS:</b> Smith et al.			
				<b>SERIAL NO.:</b> Not yet assigned.			
				<b>FILING DATE:</b> Herewith			
				<b>GROUP:</b> Not yet assigned.			
<b>U.S. PATENT DOCUMENTS</b>							
EXAM INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB/ CLASS	FILING DATE IF APPROPRIATE
M	A27	5,206,516	04/27/93	Keller et al.			
	A28	5,280,154	01/18/94	Cuomo et al.			
	A29	5,352,249	10/04/94	Vollaro			
	A30	5,353,314	10/04/94	Schaffer			
	A31	5,364,496	11/15/94	Bollinger et al.			
	A32	5,365,147	11/15/94	Shinohara et al.			
	A33	5,372,674	12/13/94	Steinberg			
	A34	5,394,061	02/28/95	Fujii			
	A35	5,397,962	03/14/95	Moslehi			
	A36	5,419,803	05/30/95	Mumola			
	A37	5,468,955	11/21/95	Chen et al.			
	A38	5,473,291	12/05/95	Brounley			
	A39	5,515,167	05/07/96	Ledger et al.			
	A40	5,534,231	07/09/96	Savas			
	A41	5,563,709	10/08/96	Poultney			
	A42	5,565,036	10/15/96	Westendorp et al.			
	A43	5,567,255	10/22/96	Steinberg			
	A44	5,567,268	10/22/96	Kadomura			
	A45	5,568,015	10/22/96	Holber et al.			
	A46	5,585,766	12/17/96	Shel			
	A47	5,610,102	03/11/97	Gardoppe et al.			
	A48	5,637,279	06/10/97	Besen et al.			
	A49	5,639,519	06/17/97	Patrick et al.			
	A50	5,647,913	07/15/97	Blalock			
✓	A51	5,662,819	09/02/97	Kadomura			
M	A52	5,681,393	10/28/97	Takagi			
<b>EXAMINER</b> Mark Paschall Primary Examiner				<b>DATE CONSIDERED</b> 3/5/03			

<b>FORM PTO - 1449</b>  <b>INFORMATION DISCLOSURE STATEMENT</b>				<b>ATTY DOCKET NO.:</b> ASX-015C4 <b>APPLICANTS:</b> Smith et al. <b>SERIAL NO.:</b> Not yet assigned. <b>FILING DATE:</b> Herewith <b>GROUP:</b> Not yet assigned.			
<b>U.S. PATENT DOCUMENTS</b>							
EXAM INIT.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
h	A53	5,688,415	11/18/97	Bollinger et al.			
	A54	5,700,297	12/23/97	Vollaro			
	A55	5,767,628	06/16/98	Keller et al.			
	A56	5,779,849	07/14/98	Blalock			
	A57	5,798,016	08/25/98	Oehrlein et al.			
	A58	5,789,867	08/04/98	Westendorp et al.			
	A59	5,811,022	09/22/98	Savas et al.			
	A60	5,814,154	09/29/98	Boitnott			
	A61	5,834,905	11/10/98	Godyak et al.			
	A62	5,874,012	02/23/99	Kanai et al.			
	A63	5,883,470	03/16/99	Hatakeyama et al.			
	A64	5,892,198	04/06/99	Barnes et al.			
	A65	5,914,278	06/22/99	Boitnott et al.			
	A66	5,932,180	08/03/99	Zhang et al.			
	A67	5,965,034	10/12/99	Vinogradov et al.			
	A68	6,063,233	05/16/00	Collins et al.			
	A69	5,364,600	11/15/94	Stiehl et al.			
	A70	5,472,561	12/05/95	Williams et al.			
	A71	5,406,177	04/11/95	Nerone			
	A72	4,748,383	05/31/88	Houkes			
	A73	4,786,352	11/22/88	Benzing			
	A74	4,859,399	08/22/89	Bussard			
	A75	5,030,889	07/09/91	El-Hamamsy et al.			
	A76	5,153,484	10/06/92	El-Hamamsy			
✓	A77	5,200,595	04/06/93	Boulos et al.			
h	A78	5,414,238	05/09/95	Steigerwald et al.			
<b>EXAMINER</b> <span style="float: right;">Mark Paschnall</span> <span style="float: right;">Primary Examiner:</span>				<b>DATE CONSIDERED</b> 3-6-05			

FORM PTO - 1449				ATTY DOCKET NO.: ASX-015C4					
INFORMATION DISCLOSURE STATEMENT				APPLICANTS: Smith et al.					
				SERIAL NO.: Not yet assigned.					
				FILING DATE: Herewith					
				GROUP: Not yet assigned.					
FOREIGN PATENT DOCUMENTS									
EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG (Y/N)
m	BA	WO90/10945	09/20/90	PCT				N	Y
	BB	SU957744 A1	02/10/96	SU				N	Y-Abstract
	BC	02260399	10/23/90	JP				Y	Y
	BD	5-166595	07/02/93	JP				N	Y-Abstract
	B1	61-139029	6/26/86	JP				N	Y-Abstract
	B2	5-144594	06/11/93	JP				N	Y-Abstract
	B3	2-260399	10/23/90	JP				N	Y-Abstract
m	B4	2022917	11/15/94	RU			9/27/89	No	Yes (Translation)
OTHER ART, JOURNAL ARTICLES, ETC.									
EXAM INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)								
m	CA	S.V. Dresvin, Physics & Tech. of Low Temp. Plasmas, H. Eckert ed, pg. 234 (1977)							
	CB	H.U. Eckert, "Analysis of Thermal Induction Plasmas between Coaxial Cylinders" <u>J. Appl. Phys.</u> 43(1):46-52 (1972)							
	CC	H.U. Eckert, "An Electrodeless Discharge at 60 Hz" <u>IEEE Trans. on Plasma Sci.</u> PS-2:308-309 (1974)							
	CD	H.U. Eckert, "The Induction Arc: A State-of-the-Art Review" <u>High Temp. Sci.</u> 6:99-134 (1974)							
	CE	H.U. Eckert, "Induction Plasmas at Low Frequencies" <u>AIAA Journal</u> 9(8):1452-1456 (1971)							
	CF	V.M. Gol'dfarb et al., "Properties of a Low-Frequency Discharge in a Transformer Plasmatron" <u>Teplofizika Vysokikh Temperatur</u> 17(4):698-702 (1979)							
	CG	E. Kandler et al., "Characterization of Plasma in an Inductively Coupled High-Dense Plasma Source" <u>Surface Coatings &amp; Tech.</u> 74 75:539-545 (1995)							
	CH	V.A. Kogan et al., "Investigation of the Prospect for the Design of Transformer-Type Plasmotrons" <u>Teplofizika Vysokikh Temperatur</u> 31(1):105-110 (1993)							
	CI	R.A. Krakowski et al., "Prospects for Using Low-Frequency Induction Plasmas for Bulk-Chemical Processing: A Systems Analysis" First INEL Workshop on Plasma Applications to Waste Treatment, Idaho Fall, Idaho, Jan. 16-17, 1991							
m	CJ	G. Soucy et al., "Parametric Study of the Decomposition of NH <sub>3</sub> for an Induction Plasma Reactor Design" <u>Plasma Chem. and Plasma Proc.</u> 15(4):693-710 (1995)							
EXAMINER				Mark Paschall Primary Examiner			DATE CONSIDERED 3/5/05		



<b>FORM PTO - 1449</b>		<b>ATTY DOCKET NO.:</b> ASX-015C4
<b>INFORMATION DISCLOSURE STATEMENT</b>		<b>APPLICANTS:</b> Smith et al.
		<b>SERIAL NO.:</b> Not yet assigned.
		<b>FILING DATE:</b> Herewith
		<b>GROUP:</b> Not yet assigned.
<b>OTHER ART, JOURNAL ARTICLES, ETC.</b>		
<b>EXAM INIT.</b>	<b>OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)</b>	
MA	CK	T.B. Reed, "Induction-Coupled Plasma Torch" <u>J. Appl. Phys.</u> 32(5):821-824 (1961)
	CL	T.B. Reed, "Growth of Refractory Crystals Using the Induction Plasma Torch" <u>J. Appl. Phys.</u> 32(12):2534-2535 (1961)
	CM	T.B. Reed, "Heat-Transfer Intensity from Induction Plasma Flames and Oxy-Hydrogen Flames" <u>J. Appl. Phys.</u> 34(8):2266-2269 (1963)
	CN	T.B. Reed, "High-Power Low-Density Induction Plasmas" <u>Communications</u> 3146-3147 (1963)
	CO	F. Maier, "Electronic Circuits for the Generation and Transfer of High-Power Pulses in Nuclear Fusion Installations" <u>IEEE Transactions on Plasma Science</u> PS-12(3): 191-198 (1984)
	CP	International Search Report dated 11/05/98 in corresponding PCT Application No. PCT/US98/13155
	CQ	Osram Endura 150W Product Information Brochure, November 1996, pp. 1-4.
	CR	Hiramatsu et al., "Generation of Strongly Ionized Aluminum Plasma in a Low-Temperature Tokamak Discharge," <u>Japanese Journal of Applied Physics</u> , Vol. 31 (July 1992) pp. 2243-2248.
	CS	Zhang et al., "A High Power Radio Frequency Transformer for Plasma Production in a Toroidal Plasma Source," <u>Rev. Sci. Instrum.</u> , Vol. 69 (January 1998) pp. 101-108.
	C1	Akulina et al., "Injection and Confinement of Plasma in a Stellarator with a Multipolar (l = 2) Helical Field," <u>Proceedings of Conference of International Atomic Energy Agency</u> (1965) pp.733-749.
	C2	Anderson, "Electrodeless Fluorescent Lamps Excited by Solenoidal Electric Field," <u>IES Transaction, Illuminating Engineering</u> (April 1969) pp. 236-242.
	C3	Ashida et al., "Measurements of Pulsed-Power Modulated Argon Plasmas in an Inductively Coupled Plasma Source," <u>J. Vac. Sci. Technol.</u> , (Mar/Apr 1996) pp. 391-397.
	C4	Asmussen, "Electron Cyclotron Resonance Microwave Discharges for Etching and Thin-Film Deposition," <u>Journal of Vacuum Science &amp; Technology A: Vacuum, Surfaces, and Films</u> , Vol. 7, No. 3 (May 1989) pp. 883-893. Abstract printed from Online Journal Publishing Service.
	C5	Bacri et al., "Influence of Departures From Complete Thermodynamic Equilibrium on Transport Coefficient Values: Application to an Oxygen Plasma," <u>Plasma Sources Sci. Technol.</u> , (1994) pp. 114-121.
	C6	Baldwin et al., "MgF <sub>2</sub> Optical Films: Ion-Beam-Assisted Deposition of Magnesium Fluoride in a Conventional Electron Beam Evaporator and the Resulting Film Properties," <u>Society of Vacuum Coaters: 40<sup>th</sup> Annual Technical Conference Proceedings</u> (1997) pp. 1-5.
	C7	Bell, "Ring Discharge Excitation of Gas Ion Lasers," <u>Applied Physics Letters</u> , Vol. 7, No. 7 (October 1965) p. 190.
	C8	Benova et al., "Axial Distributions of Metastable Atoms and Charged Particles in an Ultrahigh Frequency Argon Plasma Column at Moderate Pressures," <u>J. Appl. Phys.</u> , Vol. 79, No. 8 (April 15, 1996) pp. 3848-3852.
<b>EXAMINER</b>		<b>DATE CONSIDERED</b>
Mark Paschall		3/5/05
Primary Examiner		

FORM PTO - 1449		ATTY DOCKET NO.: ASX-015C4	
INFORMATION DISCLOSURE STATEMENT		APPLICANTS: Smith et al.	
		SERIAL NO.: Not yet assigned.	
		FILING DATE: Herewith	
		GROUP: Not yet assigned.	
OTHER ART, JOURNAL ARTICLES, ETC.			
EXAM INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)		
W	C9	Benova et al., "Theoretical Study of the Influence of a Metal Enclosure on the Parameters of a Plasma Column Sustained by a Traveling Electromagnetic Surface Wave," <u>Physica Scripta</u> , Vol. 43 (1991) pp. 68-73.	
	C10	Bhave et al., "Two- and Three-Body Ion-Electron Recombination Rate Coefficients in Neon*," <u>Aust. J. Phys.</u> , Vol. 48 (1995) pp. 503-513.	
	C11	Bishop et al., "Power Balance Measurements and Particle Loss Rate in Ohmically Heated Discharges in the C Stellarator," <u>Plasma Physics and Controlled Nuclear Fusion Research: Proceedings of Second Conference of International Atomic Energy Agency</u> , Vol. 2 (1966) pp. 673-685.	
	C12	Bluem et al., "Spatial Investigation of a Large Diameter Microwave Plasma," <u>J. Phys. D: Appl. Phys.</u> Vol. 28 (1995) pp. 1529-1533.	
	C13	Böhle et al., "On the Influence of Excited Atoms on the Electron Kinetics of a Surface Wave Sustained Argon Plasma," <u>Plasma Sources Sci. Technol.</u> Vol. 3 (1994) pp. 80-87.	
	C14	Boisse-Laporte et al., "Microwave Discharges Produced by Surface Waves in Argon Gas," <u>Journal of Physics D: Applied Physics</u> , Vol. 20 (February 14, 1987) p. 197.	
	C15	Bol, "Density Fluctuations in the Etude Stellarator," <u>The Physics of Fluids</u> , Vol. 7, No. 11 (November 1964) pp. 1855-1856.	
	C16	Bollinger et al., "Rapid, Nonmechanical, Damage-Free Figuring of Optical Surfaces Using Plasma-Assisted Chemical Etching (PACE): Part I Experimental Results," <u>SPIE Vol. 966 Advances in Fabrication and Metrology for Optics and Large Optics</u> (1988) pp. 82-90.	
	C17	Bollinger et al., "Rapid, Non-Contact Optical Figuring of Aspheric Surfaces With Plasma Assisted Chemical Etching (PACE)," <u>SPIE Vol. 1333 Advanced Optical Manufacturing and Testing</u> (1990) pp. 44-57.	
	C18	Bollinger et al., "Rapid Optical Figuring of Aspherical Surfaces With Plasma Assisted Chemical Etching (PACE)," <u>SPIE Vol. 1618 Large Optics II</u> (1991) pp. 14-21.	
	C19	Boswell et al., "Etching of Si by SF <sub>6</sub> in a Radio Frequency Double Cathode," <u>Journal of Vacuum Science &amp; Technology B: Microelectronics and Nanometer Structures</u> , Vol. 5, No. 4 (July 1987) pp. 883-888. Abstract printed from Online Journal Publishing Service.	
	C20	Bourdon et al., "Three-Body Recombination Rate of Atomic Nitrogen in Low-Pressure Plasma Flows," <u>Physical Review E</u> , Vol. 54, No. 2 (August 1996) pp. 1888-1898.	
	C21	Carruth, Jr., et al., "Method for Determination of Neutral Atomic Oxygen Flux," <u>Rev. Sci. Instrum.</u> , Vol. 61, No. 4 (1990) pp. 1211-1216.	
	C22	Chen, "Industrial Applications of Low-Temperature Plasma Physics*," <u>Phys. Plasmas</u> , Vol. 2, No. 6 (June 1995) pp. 2164-2175.	
✓	C23	Cherrington, "Chapter 8: DC Discharges-The Positive Column," <u>Gaseous Electronics and Gas Lasers</u> Pergamon Press - New York (1979) pp. 144-160.	
W	C24	Chiu et al., "What the DryScrub® System Can Do For PFC Gas Treatment?," <u>Electrochemical Technology Corp. Brochure</u> (undated).	
EXAMINER		DATE CONSIDERED	
Mark Paschall Primary Examiner		3/5/05	

FORM PTO - 1449		ATTY DOCKET NO.: ASX-015C4
INFORMATION DISCLOSURE STATEMENT		APPLICANTS: Smith et al.
		SERIAL NO.: Not yet assigned.
		FILING DATE: Herewith
		GROUP: Not yet assigned.
OTHER ART, JOURNAL ARTICLES, ETC.		
EXAM INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)	
m	C25	Coburn et al., "Ion-and Electron-Assisted Gas-Surface Chemistry - An Important Effect in Plasma Etching," <u>Journal of Applied Physics</u> , Vol. 50, No. 5 (May 1979) pp. 3189-3196. Abstract printed from Online Journal Publishing Service.
f	C26	Cohen et al., "Induced Magnetic Field Effects in Inductively Coupled Plasmas," <u>Physics of Plasma</u> , Vol. 3, No. 5 (May 1996) pp. 1839-1847. Abstract printed from Online Journal Publishing Service.
	C27	Collins et al., "Measurement of the Rate Coefficient for the Recombination of He <sup>+</sup> with Electrons*," <u>Physical Review A</u> , Vol. 6, No. 4 (October 1972) pp. 1545-1558.
	C28	Darchicourt et al., "Influence of the Radial Electron Density Profile on the Determination of the Characteristics of Surface-Wave-Produced Discharges," <u>J. Phys. D: Applied Physics</u> , Vol. 21 (1988) pp. 293-301.
	C29	Denneman, "Determination of Electromagnetic Properties of Low-Pressure Electrodeless Inductive Discharges," <u>J. Phys. D: Appl. Phys.</u> (1990) pp. 293-298.
	C30	Eckhardt et al., "Comparison of Alkali Plasma Loss Rates in a Stellarator and in a Toroidal Device With Minimum Mean-B Properties," <u>Plasma Physics and Controlled Nuclear Fusion Research: Proceedings of Second Conference of International Atomic Energy Agency</u> , Vol. 2 (1966) pp. 719-731.
	C31	Evans, "Discussion (of 'Electrodeless Fluorescent Lamps Excited by Solenoidal Electric Field' by Anderson)," <u>IES Transaction, Illuminating Engineering</u> (April 1969) pp. 242-244.
	C32	Feoktistov et al., "Self-Consistent Modeling of Low-Pressure RF Discharges in Oxygen Plasma," <u>J. Phys. D: Appl. Phys.</u> Vol. 26 (1995) pp. 1346-1353.
	C33	Ferreira, "Theory of a Plasma Column Sustained by a Surface Wave," <u>J. Phys. D: Appl. Phys.</u> (1981) pp. 1811-1830.
	C34	Ferreira, "Modeling of a Low-Pressure Plasma Column Sustained by a Surface Wave," <u>J. Phys. D: Appl. Phys.</u> , Vol. 16 (1983) p. 1673-1685.
	C35	Ferreira, "The Similarity Laws for the Maintenance Field and the Absorbed Power per Electron in Low-Pressure Surface Wave Produced Plasmas and their Extension to HF Plasmas in General," <u>Physica Scripta</u> , Vol. 38 (1988) pp. 382-399.
	C36	Ferreira et al., "Quasi-Neutral Theory of Positive Columns in Electronegative Gases," <u>J. Phys. D: Appl. Phys.</u> , Vol. 21 (1988) pp. 1403-1413.
	C37	Ferreira, "Kinetic Modeling of Microwave Discharges," <u>Microwave Discharges: Fundamentals and Applications</u> (1993) pp. 313-337.
	C38	Fiala et al., "Two-Dimensional, Hybrid Model of Low-Pressure Glow Discharges," <u>Physical Review E</u> , Vol. 49, No. 6 (June 1994) pp. 5607-5622.
W	C39	Fulton, "Application of Ion-Assisted-Deposition Using a Gridless End-Hall Ion Source for Volume Manufacturing of Thin-Film Optical Filters," <u>Optical Interference Coatings: Proceedings-SPIE The International Society for Optical Engineering</u> (1994) pp. 374-393.
EXAMINER		DATE CONSIDERED
Mark Pascual Primary Examiner		3-5-05

FORM PTO - 1449		ATTY DOCKET NO.: ASX-015C4	
INFORMATION DISCLOSURE STATEMENT		APPLICANTS: Smith et al.	
		SERIAL NO.: Not yet assigned.	
		FILING DATE: Herewith	
		GROUP: Not yet assigned.	
OTHER ART, JOURNAL ARTICLES, ETC.			
EXAM INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)		
<i>W</i>	C40	Fulton et al., "Application of Residual Stress Analysis for Ion-Assist-Deposited (IAD) Thin-Films Manufactured Using a Gridless End-Hall Ion Source," <u>Optical Interference Coatings: Technical Digest Series</u> , Vol. 17 (1995) pp. 101-103.	
	C41	Gallatin et al., "Predicted Polishing Behavior of Plasma Assisted Chemical Etching (PACE) From a Unified Model of the Temporal Evolution of Etched Surfaces," <u>SPIE Advances in Fabrication and Metrology for Optics and Large Optics</u> , Vol. 966 (1988) pp. 98-107.	
	C42	Gallatin et al., "Unified Approach to the Temporal Evolution of Surface Profiles in Solid Etch and Deposition Processes," <u>J. Appl. Phys.</u> , Vol. 65, No. 12 (June 1989) pp. 5078-5088.	
	C43	Golant et al., "Plasma Compression by a Magnetic Field in a Toroidal-Type Device," <u>Proceedings of Conference of International Atomic Energy Agency</u> (1965) pp.830-850.	
	C44	Gousset et al., "Experimental Study of a D.C. Oxygen Glow Discharge by V.U.V. Absorption Spectroscopy," <u>Plasma Chemistry and Plasma Processing</u> Vol. 7, No. 4 (1987) pp. 409-427.	
	C45	Gousset et al., "Electron and Heavy-Particle Kinetics in the Low Pressure Oxygen Positive Column," <u>J. Phys. D: Appl. Phys.</u> , Vol. 24 (1991) pp. 290-300.	
	C46	Granier et al., "Characterisation of Oxygen Discharges," <u>Journal of Physics D: Applied Physics</u> , Vol. 22 (1989) pp. 1487-1496.	
	C47	Granier et al., "Diagnostics in O <sub>2</sub> Helicon Plasmas for SiO <sub>2</sub> Deposition," <u>Plasma Sources Sci. Technol.</u> , Vol. 6 (1997) pp. 147-156.	
	C48	Hartney et al., "Critical Review: Oxygen Plasma Etching for Resist Stripping and Multilayer Lithography," <u>J. Vac. Sci. Technol.</u> , pp. I (Jan/Feb 1989).	
	C49	Heimer et al., "Ponderomotive Transport of Charge in the Induction Plasma," <u>J. Vac. Sci. Technol.</u> , (Jan/Feb 1994) pp. 507-511.	
	C50	Henriksen et al., "Electromagnetic Field in Electrodeless Discharge," <u>Journal of Applied Physics</u> , Vol. 42, No. 13 (December 1971) pp. 5460-5464.	
	C51	Heshmaty et al., "Approaches Explored for Producing a Variety of Ion-Assisted-Deposited Thin-Film Coatings Using an End-Hall Ion Source," <u>Developments in Optical Component Coatings: Proceedings of SPIE Conference</u> , Vol. 2776 (1996) pp. 114-125.	
	C52	Hopwood, "Review of Inductively Coupled Plasmas for Plasma Processing," <u>Plasma Sources Sci. Technol.</u> , (1992) pp. 109-116.	
	C53	Hopwood et al., "Electromagnetic Fields in a Radio-Frequency Induction Plasma," <u>Journal of Vacuum Science &amp; Technology A: Vacuum, Surfaces, and Films</u> , Vol. 11, No. 1 (January 1993) pp. 147-151. Abstract printed from Online Journal Publishing Service.	
<i>W</i>	C54	Hopwood et al., "Langmuir Probe Measurements of a Radio Frequency Induction Plasma," <u>Journal of Vacuum Science &amp; Technology A: Vacuum, Surfaces, and Films</u> , Vol. 11, No. 1 (January 1993) pp. 152-156. Abstract printed from Online Journal Publishing Service.	
<i>W</i>	C55	Kita et al., "Rocket Observation of Atomic Oxygen and Night Airglow: Measurement of Concentration with an Improved Resonance Fluorescence Technique," <u>Annales Geophysicae</u> , Vol. 14 (1996) 227-237.	
EXAMINER		Primary Examiner	DATE CONSIDERED 3-5-05

FORM PTO - 1449		ATTY DOCKET NO.: ASX-015C4
INFORMATION DISCLOSURE STATEMENT		APPLICANTS: Smith et al.
		SERIAL NO.: Not yet assigned.
		FILING DATE: Herewith
		GROUP: Not yet assigned.
OTHER ART, JOURNAL ARTICLES, ETC.		
EXAM INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)	
M	C56	Kolobov et al., "Electron Kinetics and Non-Joule Heating in Near-Collisionless Inductively Coupled Plasmas," <u>Physical Review E</u> , Vol. 55, No. 3 (March 1997) 3408-3422.
	C57	Kortshagen et al., "Determination of Electron Energy Distribution Functions in Surface Wave Produced Plasmas: I. Modeling," <u>J. Phys. D: Appl. Phys.</u> , Vol. 24 (1991) pp. 1571-1584.
	C58	Kortshagen et al., "Determination of Electron Energy Distribution Functions in Surface Wave Produced Plasmas: II. Measurements," <u>J. Phys. D: Appl. Phys.</u> , Vol. 24 (1991) pp. 1585-1593.
	C59	Kortshagen, "Experimental and Theoretical Determination of Electron Energy Distribution Functions in Surface Wave Plasmas," <u>Microwave Discharges: Fundamentals and Applications</u> (1993) pp. 303-312.
	C60	Kouznetsov et al., "Modeling Electronegative Discharges at Low Pressure," <u>Plasma Sources Science &amp; Technology</u> , Vol. 5, No. 4 (Nov. 1996) Abstract printed from Insitutue for Scientific Information.
	C61	Lee et al., "Global Model for High Pressure Electronegative Radio-Frequency Discharges," <u>Journal of Vacuum Science &amp; Technology A-Vacuum Surfaces and Films</u> Vol. 15, No. 1 (Jan.-Feb. 1997) 113-126. Abstract printed from Institute for Scientific Information.
	C62	Lichtenberg et al., "Modeling Plasma Discharges at High Electronegativity," <u>Plasma Sources Sci. Technol.</u> Vol. 6 (1997) 437-449.
	C63	Lister et al., "Modeling of Inductively Coupled Discharges With Internal and External Coils," <u>Plasma Sources Sci. Technol.</u> Vol. 1 (1992) 67-73.
	C64	Malik et al., "Overview of Plasma Source Ion Implantation Research at University of Wisconsin-Madison," <u>Journal of Vacuum Science &amp; Technology B: Microelectronics and Nanometer Structures</u> Vol. 12, No. 2 (March 1994) 843-849. Abstract printed from Online Journal Publishing Service.
	C65	Margot et al., "Modeling of Surface-Wave-Sustained Plasmas in Static Magnetic Fields: A Tool for the Study of Magnetically Assisted HF Plasmas," <u>Microwave Discharges: Fundamentals and Applications</u> (1993) 141-159.
	C66	Michelt et al., "Measurement of the Rotational Temperature of Oxygen in a High-Power Inductively Coupled Plasma," <u>J. Phys. D: Appl. Phys.</u> Vol. 28 (1995) 2600-2606.
	C67	Moisan et al., "A Small Microwave Plasma Source for Long Column Production Without Magnetic Field," <u>IEEE Transactions on Plasma Science</u> , Vol. PS-3, No. 2 (June 1975) p. 55.
	C68	Moisan et al., "Plasma Sources Based on the Propagation of Electromagnetic Surface Waves," <u>J. Phys. D: Appl. Phys.</u> Vol. 24 (1991) pp. 1025-1048.
	C69	Morrow et al., "In Situ Measurement of Atomic Nitrogen in the Ground ( <sup>4</sup> S) and Metastable ( <sup>2</sup> D) and ( <sup>2</sup> P) States by Resonance Fluorescence for Project Aries," <u>Centre for Research in Experimental Space Science</u> (April 1981).
↓	C70	Niederwald et al., "IAD of Oxide Coatings at Low Temperature: A Comparison of Processes based on Different Ion Sources," <u>Proc. SPIE</u> Vol. 3133 (1997) pp. 205-213.
M	C71	Okada et al., "Microwave Determination of the Coefficient of Dissociative Recombination of Ar <sub>2</sub> in AR Afterglow," <u>J. Phys. D: Appl. Phys.</u> Vol. 26 (1993) 1680-1686.
EXAMINER		DATE CONSIDERED

Mark Paschall  
Primary Examiner

3-5-05

FORM PTO - 1449		ATTY DOCKET NO.: ASX-015C4
INFORMATION DISCLOSURE STATEMENT		APPLICANTS: Smith et al.
		SERIAL NO.: Not yet assigned.
		FILING DATE: Herewith
		GROUP: Not yet assigned.
OTHER ART, JOURNAL ARTICLES, ETC.		
EXAM INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)	
W	C72	Ono et al., "Effect of Annealing on Mechanical Properties of Electron-Irradiated Aluminum single Crystals at 23°K <sup>1</sup> ," <u>Applied Physics Letters</u> Vol. 7, No. 7 (October 1, 1965) pp. 191.
	C73	Pawlewicz et al., "Low-Energy High-Flux Reactive Ion Assisted Deposition of Oxide Optical Coatings: Performance, Durability, Stability and Scalability," <u>SPIE Proceedings 2261</u> (1994) 1-12.
	C74	Perry et al., "The Application of the Helicon Source of Plasma Processing," <u>Journal of Vacuum Science &amp; Technology B: Microelectronics and Nanometer Structures</u> Vol. 9, No. 2 (March 1991) 310-317. Abstract printed from Online Journal Publishing Service.
	C75	Persson "Inertia-Controlled Ambipolar Diffusion," <u>The Physics of Fluids</u> Vol. 5, No. 12 (December 1962) 1625-1632.
	C76	Persson "Brush Cathode Plasma - A Well-Behaved Plasma," <u>Journal of Applied Physics</u> Vol. 36, No. 10 (October 1965) 3086-3094.
	C77	Phelps "Role of Molecular Ions, Metastable Molecules, and Resonance Radiation in the Breakdown of Rare Gases," <u>The Physical Review</u> Vol. 117, No. 3 (February 1, 1960) 619-632.
	C78	Piejak et al., "A Simple Analysis of an Inductive RF Discharge," <u>Plasma Sources, Science and Technology</u> , Vol. 1, No. 3 (1992) pp. 179-186.
	C79	Piejak et al., "The Electric Field and Current Density in a Low-Pressure Inductive Discharge Measured with Different B-dot Probes," <u>J. Appl. Phys.</u> Vol. 81, No. 8 (April 15, 1997) 3416-3421.
	C80	Popov "Characteristics of Electron Cyclotron Resonance Plasma Sources," <u>Journal of Vacuum Science &amp; Technology A: Vacuum, Surfaces, and Films</u> Vol. 7, No. 3 (May 1989) 894-898. Abstract printed from Online Journal Publishing Service.
	C81	Rapp et al., "Charge Exchange Between Gaseous Ions and Atoms," <u>The Journal of Chemical Physics</u> Vol. 37, No. 11 (December 1, 1962) 2631-2645.
	C82	Resonance Ltd., <u>Operation Manual for Vacuum Monochromator Model #VS2FS</u> (Sept. 1993).
	C83	Resonance Ltd., <u>Operation Manual for RF Powered Line Sources</u> (undated).
	C84	Sato, "Plasma Density Profile and Electron Temperature in Discharge Positive Columns at Intermediate Pressures: Examination of Ingold's Approximation," <u>J. Phys. D: Appl. Phys.</u> Vol. 26 (1993) 1687-1690.
	C85	Schiffer et al., "Negative-Oxygen-Ion Detection by a Crossed-Beam Photodetachment Technique," <u>Plasma Sources Sci. Technol.</u> Vol. 4 (1995) 345-352.
	C86	Self et al., "Static Theory of a Discharge Column at Intermediate Pressures," <u>The Physics of Fluids</u> Vol. 9, No. 12 (December 1966) 2486-2492.
U	C87	Sirghi et al., "Nonlocal Particle Loss Effects on the Electron Kinetics in a Direct Current Helium Diffusion-Controlled Positive Column," <u>Phys. Plasmas</u> Vol. 4, No. 4 (April 1997) 1160-1165.
m	C88	Smirnov et al., "Resonance Charge Transfer in Inert Gases," <u>Soviet Physics-Technical Physics</u> Vol. 10, No. (1965) 83-92.
EXAMINER		DATE CONSIDERED
Mark Paschall Primary Examiner		3/5/05

FORM PTO - 1449		ATTY DOCKET NO.: ASX-015C4	
INFORMATION DISCLOSURE STATEMENT		APPLICANTS: Smith et al.	
		SERIAL NO.: Not yet assigned.	
		FILING DATE: Herewith	
		GROUP: Not yet assigned.	
OTHER ART, JOURNAL ARTICLES, ETC.			
EXAM INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)		
m	C89	Smith, "Section 9.6: Plasma Chemistry," <u>Thin-Film Deposition: Principles and Practice</u> McGraw-Hill-New York: (1995) pp. 616-617.	
↑	C90	Stodiek et al., "Plasma Confinement in Low-Density C Stellarator Discharges," <u>Proceedings of a Conference on Plasma Physics and Controlled Nuclear Fusion Research</u> CN-21/120, International Atomic Energy Agency (1965) pp. 687-703.	
	C91	Stowers et al., "Review of Precision Surface Generating Processes and Their Potential Application to the Fabrication of Large Optical Components," <u>SPIE Advances in Fabrication and Metrology for Optics and Large Optics</u> , Vol. 966, (1988) pp. 62-73.	
	C92	Suchel et al., "Properties of TiO <sub>2</sub> and SiO <sub>2</sub> Films Prepared by Ion-Assisted Deposition Using a Gridless End-Hall Ion Source," <u>Society of Vacuum Coaters: 36<sup>th</sup> Annual Technical Conference Proceedings</u> (1993) pp. 82-87.	
	C93	Sugai et al., "Diagnostics and Control of Radicals in an Inductively Coupled Etching Reactor," <u>Journal of Vacuum Science &amp; Technology A</u> , Vol. 13, No. 3, Pt. 1 (May/June 1995) pp. 887-893.	
	C94	Toader "On the Constricted Neon Positive Column," <u>J. Phys. D: Appl. Phys.</u> , Vol. 28 (1995) 75-80.	
	C95	Tuszewski et al., "Composition of the Oxygen Plasmas from Two Inductively Coupled Sources," <u>J. Vac. Sci. Technol. A</u> Vol. 13, No. 3 (May/June 1995) 839-842.	
	C96	Tuszewski "An Electronegative Inductive Discharge Instability," <u>J. Appl. Phys.</u> Vol. 79, No. 12 (June 15, 1996) 8967-8975.	
	C97	Tuszewski, "Enhanced Radio Frequency Field Penetration in an Inductively Coupled Plasma," <u>Physical Review Letters</u> Vol. 77, No. 7 (August 12, 1996) 1286-1289.	
	C98	Tuszewski, "Inductive Electron Heating Revisited*," <u>Phys. Plasmas</u> Vol. 4, No. 5 (May 1997) 1922-1928.	
	C99	Vahedi et al., "Analytic Model of the Ion Angular Distribution in a Collisional Sheath," <u>Journal of Vacuum Science &amp; Technology A: Vacuum, Surfaces, and Films</u> Vol. 11, No. 4 (July 1993) 1275-1282. Abstract printed from Online Journal Publishing Service.	
	C100	Vahedi "Modeling and Simulation of RF Discharges Used for Plasma Processing," <u>Dissertation Submitted in Partial Satisfaction of Requirement for Ph.D. in Electrical Engineering and Computer Science from University of California at Berkeley</u> (1993)	
	C101	Vialle et al., "Kinetics of O( <sup>1</sup> S) and O( <sup>1</sup> D) Metastable Atoms in a DC Oxygen Glow Discharge," <u>J. Phys. D: Appl. Phys.</u> , Vol. 24 (1991) pp. 301-308.	
	C102	Višek, "A Collisional-Radiative Model Applicable to Argon Discharges Over a Wide Range of Conditions: Formulation and Basic Data," <u>J. App. D: Appl. Phys.</u> , Vol. 22 (1989) 623-631.	
↓	C103	Whitmer et al., "Effects of a Velocity-Dependent Collision Frequency on Wave-Plasma Interactions," <u>The Physics of Fluids</u> , Vol. 9 (April 1966) 768-773.	
m	C104	Yoshikawa et al., "Ion Heating in the C Stellarator," <u>Plasma Physics and Controlled Nuclear Fusion Research: Proceedings of Second Conference of International Atomic Energy Agency</u> , (1965) 925-939.	
EXAMINER		DATE CONSIDERED	
Mark Paschall Primary Examiner		3-5-15	

FORM PTO - 1449		ATTY DOCKET NO.: ASX-015C4
INFORMATION DISCLOSURE STATEMENT		APPLICANTS: Smith et al.
		SERIAL NO.: Not yet assigned.
		FILING DATE: Herewith
		GROUP: Not yet assigned.
OTHER ART, JOURNAL ARTICLES, ETC.		
EXAM INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)	
M	C105	Zarowin et al., "Quasi-CW, High Numerical Aperture, Inductively Excited Ion Laser*, " <u>Applied Physics Letters</u> , Vol. 11, No. 2 (July 15, 1967) pp. 47-48.
	C106	Zarowin, "Relation Between the RF Discharge Parameters and Plasma Etch Rates, Selectivity, and Anisotropy," <u>J. Vac. Science Technology</u> (Oct.-Dec. 1984) pp. 1537-1549.
	C107	Zarowin, "A Theory of Plasma-Assisted Chemical Vapor Transport Processes," <u>J. Appl. Phys.</u> Vol. 57, No. 3 (February 1985) pp. 929-942.
	C108	Zarowin et al., "Rapid, Non-Mechanical, Damage Free Figuring of Optical Surfaces Using Plasma Assisted Chemical Etching (PACE): Part II Theory & Process Control, <u>SPIE Vol. 966 Advances in Fabrication and Metrology for Optics and Large Optics</u> (1988) pp. 91-97.
	C109	Zarowin et al., "Rapid, Non-Contact Damage Free Shaping of Optical & Other Surfaces With Plasma Assisted Chemical Etching," <u>IEEE 43d Annual Symposium on Frequency Control</u> (1989) pp. 623-626.
	C110	Zarowin, "A Comparison Using Surface Evolution Theory of the Smoothing and Figuring of Optics by Plasma Assisted Chemical Etching and Ion Milling," <u>SPIE Vol. 1618 Large Optics II</u> (1991) pp. 22-26.
	C111	Zhang et al., "Modification of the Density Profile in a Toroidal Plasma Source Using a Bias Electric Field," <u>Appl. Phys. Lett.</u> , Vol. 70, No. 23 (June 9, 1997) pp. 3090-3092.
	C112	Zhelyazkov et al., "Axial Structure of Low-Pressure High-Frequency Discharges Sustained by Traveling Electromagnetic Surface Waves," <u>Physics Reports-Review Section of Physics Letters</u> , (1995) pp. 79-201.
	C113	Hirose et al., "STOR II A Tokamak for Plasma Heating Studies," Plasma Physics Laboratory, University of Saskatchewan, April 1981, pp. 11-14.
	C114	Osram ECG-SPOT Brochure, February 1997, pp. 1-12.
	C115	Cayless et al., " <u>Lamps and Lighting</u> ," Third Edition, pp. 280-286.
	C116	"International Lighting Review, Induction Lighting," <u>The Global Lighting Magazine</u> , April 1996.
	C117	"The Advanced Energy PE 2500 W, 100 kHz Generator with Load Matching User Manual," September 1989
	C118	Kassakian et al., <u>Principles of Power Electronics</u> , 1991, Chapter 1, pp. 1-8.
	C119	Lieberman et al., <u>Principles of Plasma Discharges and Material Processing</u> ; Chapter 12 "Inductive Discharges," pp. 387-389.
W	C120	Benesch, <u>Breakdown in the Pretext Tokamak</u> , "Chapter Two - The Machine," June 1981, pp. 15-16.
W	C121	Kogan et al., "Research into Potential for Creating Transformer Type Plasmatrons," <u>Teplofizika Vysokikh Temperatur</u> , Vol. 31, No. 1, 1993, pp. 1-8.
EXAMINER	Mark Pasche Primary Examiner	
	DATE CONSIDERED	3/5/05